	Application No.	Applicant(s)	(GW)	
Notice of Allowability	10/800,348	YAMASHITA, TENKO	YAMASHITA, TENKO	
	Examiner	Art Unit		
	Theresa T. Doan	2814		
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in thi i) or other appropriate communic RIGHTS. This application is subj	is application. If not included attention will be mailed in due cou	rse. THIS	
1. This communication is responsive to <u>04/01/05</u> .	•			
2. 🔀 The allowed claim(s) is/are <u>1-16</u> .				
3. X The drawings filed on <u>02 August 2004</u> are accepted by th	e Examiner.			
 4. ☐ Acknowledgment is made of a claim for foreign priority of a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have a linternational Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	re been received. re been received in Application N	lo	from the	
Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDONI THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		eply complying with the require	ements	
5. A SUBSTITUTE OATH OR DECLARATION must be subr INFORMAL PATENT APPLICATION (PTO-152) which give	nitted. Note the attached EXAMI ves reason(s) why the oath or de	NER'S AMENDMENT or NOTI claration is deficient.	CE OF	
6. CORRECTED DRAWINGS (as "replacement sheets") mu	ıst be submitted.			
(a) including changes required by the Notice of Draftsper	rson's Patent Drawing Review (I	PTO-948) attached		
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date	<u>.</u> .			
(b) including changes required by the attached Examiner Paper No./Mail Date	's Amendment / Comment or in	the Office action of		
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in			k) of	
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT	osit of BIOLOGICAL MATER	AL must be submitted. Note	the	
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Sumi Paper No./Ma	il Date	52)	
 Information Disclosure Statements (PTO-1449 or PTO/SB/ Paper No./Mail Date 3/12/04 & 8/10/04 	′08), 7. ⊠ Examiner's Am —	endment/Comment		
4. Examiner's Comment Regarding Requirement for Deposit		tement of Reasons for Allowar	nce	
of Biological Material	9. 🔲 Other			

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DETAILED ACTION

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1. Applicant's election of Group I claims 1-16 in the reply filed on 04/01/05 is acknowledged. Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

EXAMINER'S AMENDMENT

2. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

This application is in condition for allowance except for the presence of claims 17-19 non-elected without traverse. Accordingly, claims 17-19 have been cancelled.

Reasons for Allowance

- 3. Claims 1-16 are allowed.
- 4. The following is an examiner's statement of reasons for allowance:

The prior art of record fails to disclose the combination of a method of forming a semiconductor on insulator (SOI) substrate having at least two exposed surface crystal orientations recited in the base claims 1 and 8. Specifically, the combination of the

process comprising a step of providing an SOI substrate having a first silicon layer with a surface having a first crystal orientation located on a first buried oxide layer, the buried oxide layer being located on a silicon substrate having a surface with a second crystal orientation; selectively removing the first silicon layer and the fist buried oxide layer to expose a first surface portion of the silicon substrate; epitaxially growing a second silicon layer over the first surface portion of the silicon substrate, the second silicon layer having a surface with a second crystal orientation; and forming a second buried oxide layer in the second silicon layer.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Theresa T. Doan whose telephone number is (571) 272-1704. The examiner can normally be reached on Monday to Friday from 7:00AM - 4:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, WAEL FAHMY can be reached on (571) 272-1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

TD May 2, 2005.

PHAT X. CAC
PRIMARY EXAMINER

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